



Advanced EUV and X-Ray Optics

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Message from the Guest Editors

Dear Colleagues,

More than a century after the discovery of X-ray radiation by Wilhelm Conrad Röntgen in 1895, short wavelength radiation in the extreme ultraviolet to soft X-ray region of the electromagnetic spectrum has been developed into an inevitable and unique probe for fundamental research in physics, chemistry, astronomy and life sciences, as well as a driver of technological development, e.g., in advanced microscopy and lithography systems.

This Special Issue of the journal *Applied Sciences* “Advanced EUV and X-Ray Optics” calls for research articles covering such new ideas and recent advances in the design, development, fabrication and application of EUV and/or soft X-ray optical elements and systems with unprecedented parameters.

Keywords: ultrafast optics; chirping; pulse shaping; multilayer mirrors; diffractive optics; design and fabrication of multilayer optics; optimization of multilayer optics; EUV and soft X-rays; metrology of multilayer optics; lithography optics; polarizers; FEL optics

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